

- L11: (29) 10 and (organic.clm. or polymer.clm.)
- L12: (20) 11 and (etch\$3 or pattern\$3)
- L13: (7) 12 and ((silicon adj based) or polysiloxane or silsesquioxane)
- L14: (9) (*6,324,091" or (*6,320,200" or (*6,348,700" or (*4,663,270" or
- L15: (34202) 2 and electrode.clm.
- L16: (0) 15 and (silicon adj based adj (mask or photoresist or resist))
- L17: (14045) 15 and (resist or mask or photoresist)
- L18: (658) 17 and ((mask or resist or pattern) near (organic or polymer or se
- L19: (485) 18 and ((pattern\$3 or etch\$3) adj2 (organic or polymer or semicon
- L20: (99) 19 and ((pattern\$3 or etch\$3) adj2 (organic or polymer))
- L21: (29) 20 and ((pattern\$3 or etch\$3) adj2 (organic or polymer)).clm.

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20 and ((pattern\$3 or etch\$3) adj2 (organic or polymer)).clm.

USPTO/USPO/PUBS

Patents
Detailed search OR
Highlight all items in list

U	I	Document ID	Issue Date	Pages	Title	Current CR	Current Xref	Retrieval C	Inventor	S	C	E	P	Q	W	
1	<input checked="" type="checkbox"/>	US 20030224611	20031204	60	Manufacturing method of semiconductor devices by using a mask or resist	438/706			Seta, Shoji et al.	<input checked="" type="checkbox"/>	US 21					
2	<input checked="" type="checkbox"/>	US 20030207521	20031106	56	Manufacturing use of a mask or resist	438/200			Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
3	<input checked="" type="checkbox"/>	US 20030165756	20030904	29	Method of manufacturing electronic device	430/5	430/22; 430/311		Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
4	<input checked="" type="checkbox"/>	US 20030151118	20030814	18	Aperture masks for circuit fabrication	257/620	257/40; 257/618;		Baude, Paul F. et al.	<input checked="" type="checkbox"/>	US 21					
5	<input checked="" type="checkbox"/>	US 20030052061	20030320	6	METHOD FOR PRODUCING ACTIVE OR PASSIVE COMPONENTS ON A PLATE	216/24			KOOPS, HANS WILFRIED PETER	<input checked="" type="checkbox"/>	US 21					
6	<input checked="" type="checkbox"/>	US 20030048256	20030313	30	Computing device with roll up components	345/168			Salmon, Peter C.	<input checked="" type="checkbox"/>	US 21					
7	<input checked="" type="checkbox"/>	US 20030036293	200303220	31	Method for manufacturing a semiconductor device	438/760	430/701; 438/942		Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
8	<input checked="" type="checkbox"/>	US 20030022446	200303130	19	Nonvolatile semiconductor memory device and manufacturing method	438/257	257/315; 257/E21.682;		Lee, Seong-Soo et al.	<input checked="" type="checkbox"/>	US 21					
9	<input checked="" type="checkbox"/>	US 20030003715	20030102	8	Fabrication of molecular electronic circuit by imprinting	438/800			Chen, Yong	<input checked="" type="checkbox"/>	US 21					
10	<input checked="" type="checkbox"/>	US 20020086232	20020704	13	Electronically active primer layers for thermal patterning	430/200	430/311; 430/312;		Nirmal, Manoj et al.	<input checked="" type="checkbox"/>	US 21					
11	<input checked="" type="checkbox"/>	US 20020059899	20020523	60	Manufacturing method of semiconductor devices by using a mask or resist	117/79	117/64; 257/E21.252;		Seta, Shoji et al.	<input checked="" type="checkbox"/>	US 21					
12	<input checked="" type="checkbox"/>	US 20020052122	20020502	56	Method of manufacturing a semiconductor device	438/758			Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
13	<input checked="" type="checkbox"/>	US 2001015454	20010823	19	Nonvolatile semiconductor memory device and manufacturing method	257/315	257/314; 257/316;		Lee, Seong-soo et al.	<input checked="" type="checkbox"/>	US 21					
14	<input checked="" type="checkbox"/>	US 6645856	20031111	30	Method for manufacturing a semiconductor device using a mask or resist	438/671	430/313; 430/5;		Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
15	<input checked="" type="checkbox"/>	US 6605542	20030612	56	Manufacturing method of semiconductor devices by using a mask or resist	438/700	257/E21.252; 257/E21.579;		Seta, Shoji et al.	<input checked="" type="checkbox"/>	US 21					
16	<input checked="" type="checkbox"/>	US 6596656	20030722	54	Manufacturing method of photomasks with an opaque pattern	438/5	438/945;		Tanaka, Toshihiko et al.	<input checked="" type="checkbox"/>	US 21					
17	<input checked="" type="checkbox"/>	US 6503008	20030624	18	Nonvolatile semiconductor memory device and manufacturing method	438/257	257/E21.682; 257/E21.107;		Lee, Seong-Soo et al.	<input checked="" type="checkbox"/>	US 21					

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